

Dear Colleagues,

Oblon and Maiwald are pleased to invite you to:

June Symposium on U.S. and European Patent Practice

Monday, June 5, 2017 at the Kimpton Lorien Hotel in Alexandria, VA

U.S. and European patent systems have their pros and cons, which do not always neatly align. Applicants for U.S. and European patents need to be aware of the peculiarities and most recent developments in each system in order to achieve the best results.

For more than 25 years, Oblon has obtained more U.S. patents for its clients each year than any other law firm in the world. Oblon offers all aspects of IP services, and has one of the top post-grant practice groups in the U.S. Maiwald, one of the top ranked IP firms in Germany, covers the full spectrum of IP-related matters in Germany and before the European patent/trademark offices and courts. Both firms are well known for excellence in patent law.

At the joint symposium, we will together examine current aspects of IP practice including prosecuting applications and defending patents in the U.S. In particular, the symposium will address the following important topics for today's practitioners:

- New developments in patent law: Recent developments at the U.S. Supreme Court, the European Patent Office, and in the European Unified Patent Court, functional language, indefiniteness, and patentable subject matter;
- 2. Efficiency and effectiveness in patent prosecution; and
- 3. U.S. Post-grant proceedings and European Opposition proceedings.

For more detail, see:

http://www.maiwald.eu/oblon-and-maiwald-joint-symposium

http://www.oblon.com/events/oblon-and-maiwald-joint-symposium

This complimentary symposium will take place on Monday, June 5, 2017 at the Kimpton Lorien Hotel in Alexandria, VA, starting at 10:00AM and ending at 5:00PM. Lunch will be provided at Brabo and the day will conclude with a casual reception. CLE will be requested.

If you plan to attend, please register in advance by returning the registration form included herewith or send an e-mail to patentconference@oblon.com or empfang@maiwald.eu. The final registration deadline is May 20, 2017 and attendance is limited to 50 participants.

We look forward to welcoming you and your colleagues in Alexandria on June 5, 2017.

Sincerely,

Oblon, McClelland, Maier & Neustadt, L.L.P. & Maiwald Patentanwalts GmbH



Event day and location

Monday, June 5, 2017 10:00AM – 5:00PM Kimpton Lorien Hotel 1600 King Street Alexandria, VA 22314 T: 703-894-3434 http://www.lorienhotelandspa.com

Contact:

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Oblon, McClelland, Maier & Neustadt, L.L.P.

For more than 25 years, Oblon has obtained more U.S. patents for its clients each year than any other law firm in the world. Oblon offers all aspects of IP services, including prosecution, opinions, counseling, IP transactions, litigation, and representation in post-grant proceedings. Oblon has one of the top Patent Trial and Appeal Board practice groups in the U.S. and Oblon's attorneys and have developed a strong U.S. IP presence for a number of foreign and domestic companies. Many of Oblon's attorneys have advanced degrees in science or engineering, adding a high degree of technical understanding to their legal knowledge. Oblon also maintains strong connections with people in the neighboring U.S. Patent and Trademark Office, and has hired several former U.S. Patent Examiners and Administrative Patent Judges to represent its clients in patent matters before the Office.

Primary Oblon Contact: Kirsten Grüneberg (kgruneberg@oblon.com; direct: 703 412 7050)

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Maiwald Patentanwaltsgesellschaft mbH

Maiwald, one of the top IP firms in Germany, covers the full spectrum of IP-related matters. We draft and file patent and trademark applications and defend and enforce our clients' intellectual property rights in Germany, Europe, and throughout the world. Our highly-specialized interdisciplinary teams of technically-qualified patent attorneys and attorneys-at-law provide combined expertise across a wide range of disciplines: life sciences, chemistry and physics; mechanical, electrical, electronic and aeronautic engineering; communication technologies; infringement litigation, trademark, design, contract, and copyright law. Maiwald's fresh approach opens up new perspectives, and delivers customized solutions that safeguard our clients' IP rights in order to promote the success of their businesses.

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Scheduled Program - June 5, 2017

Sign-in and coffee (9:30 am)

Morning Session (10:00 am)

Welcome address

Functional Language in U.S. Patent Claims *David M. Longo*

Functional Claim Language at the EPO and elsewhere in Europe *Ralk Kotitschke*

Recent Patent Developments before the U.S. Supreme Court Andrew M. Ollis

Recent Case Law of the EPO and Outlook on the Upcoming UPC *TBD*

Lunch (12:00 pm)

Brabo restaurant adjacent to the Lorien Hotel

Afternoon Session (1:30 pm)

Patent Eligible Subject Matter in the U.S. *James Love*

Judicial Exceptions and Patent Eligibility (Biotech/Pharma) *Kirsten A. Grüneberg*

Patent Eligible Subject Matter in Europe (Biotech/Pharma)

Alexander Ortlieb

Coffee Break (3:00 pm)

Efficiency and Effectiveness in Patent Prosecution (U.S.) *Eric Myers*

Efficiency and Effectiveness in Patent Prosecution (Europe) *TBD*

Post-grant Proceedings in the U.S. *Kirsten A. Grüneberg*

Post-grant Proceedings before the EPO, German Courts, and the UPC Derk Vos

Cocktails (5:00 pm)



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